

SEMICONDUCTOR STRUCTURE AND METHOD FOR MANUFACTURING SAME

ABSTRACT

Disclosed are a semiconductor structure and a preparation method therefor. The semiconductor structure (100) comprises: a functional structure (11) and a first mark structure (121), which are located on a substrate (10), a feature size of the functional structure (11) being the same as a feature size of the first mark structure (121); and a first dielectric layer (20), which is located at the functional structure (11) and the first mark structure (121), the thickness of the first dielectric layer at the functional structure (11) being different from the thickness of the first dielectric layer at the first mark structure (121).

[Fig. 1]